WEST Search History

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DATE: Tuesday, January 24, 2006

Hide?	Set Name	Query	Hit Count
		DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ	
☐	L18	((metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2') same ((post CMP) or (after CMP) or (after polish$3)) same surfactant same hydrophilic) and ((multiple or plural$3) with polish$3)	2
☐	L17	l15 and octanol	5
☐	L16	L13 and alcohol and clean$	55
☐	L15	L13 and alcohol	65
☐	L14	L13 and alkohol	0
☐	L13	((metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2') and ((post CMP) or (after CMP) or (after polish$3)) and surface and surfactant and hydrophilic and (multiple or plural$3) same polish$3)	90
☐	L12	((metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2') same ((post CMP) or (after CMP) or (after polish$3)) same surface same surfactant same hydrophilic) and ((multiple or plural$3) with polish$3)	2
☐	L11	(metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2') same ((post CMP) or (after CMP) or (after polish$3)) same surface same surfactant same hydrophilic same ((multiple or plural$3) with polish$3)	0
☐	L10	(metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2') same ((post CMP) or (after CMP) or (after polish$3)) same surface same surfactant same hydrophilic same (multiple or plural$3)	2
☐	L9	L8 and alcohol	13
☐	L8	(metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2') same ((post CMP) or (after CMP) or (after polish$3)) same surface same surfactant same hydrophilic	21
☐	L7	L6 and alcohol	13
☐	L6	(wafer or semiconductor or substrate) same (metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2') same ((post CMP) or (after CMP) or (after polish$3)) same surface same surfactant same hydrophilic	18
		DB=USPT; PLUR=YES; OP=ADJ	
☐	L5	l2 and alcohol	7
☐	L4	L3 and alcohol	0

☐   L3   6444583.pn.   1

DB=PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ

☐   L2   ((wafer or semiconductor or substrate) with (metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2') same ((post CMP) or (after CMP) or (after polish$3)) same surface same surfactant same hydrophilic)   17

☐   L1   ((wafer or semiconductor or substrate) with (metal or copper or aluminum or tungsten or (low K) or oxide or nitride or Cu or Al or W or Ti or 'SiO.sub.2') same (((post CMP) or (after CMP) or (after polish$3)) with surface with surfactant with hydrophilic))   0

END OF SEARCH HISTORY